

2015/2016 SEMESTER 1 – SEMESTRAL EXAMINATION

Course : Diploma in Electronics, Computer and Communications
Engineering

Module : EG3010 – Microelectronics

Aug/Sep 2015

Time Allowed : 2 hrs

INSTRUCTIONS TO CANDIDATES

1. This exam paper consists of **SEVEN (7)** pages including this page.
2. This examination paper contains 2 sections.

Section A: 2 Questions
Section B: 3 Questions
3. Answer ALL questions in Section A.
Answer ANY 2 questions in Section B.
4. Mask Layout Encoding Table and Stick Diagram Coding Table are provided on Page 7.

SECTION A – ANSWER ALL QUESTIONS (50 Marks)Question 1

- (a) Figure Q1 shows a METAL2 wire segment, not drawn to scale. If it has a sheet resistance of $R_s = R_{sM} \Omega/\square$ and a relative capacitance $0.2 \square C_g$, compute the following:
- resistance of the wire, in terms of R_{sM} . (4 marks)
 - capacitance due to the wire, in terms of $\square C_g$. (4 marks)
 - time taken to travel through this segment of the wire, in terms of τ , where $\tau = R_{sn} * \square C_g$ and R_{sn} is the sheet resistance of polysilicon. (4 marks)

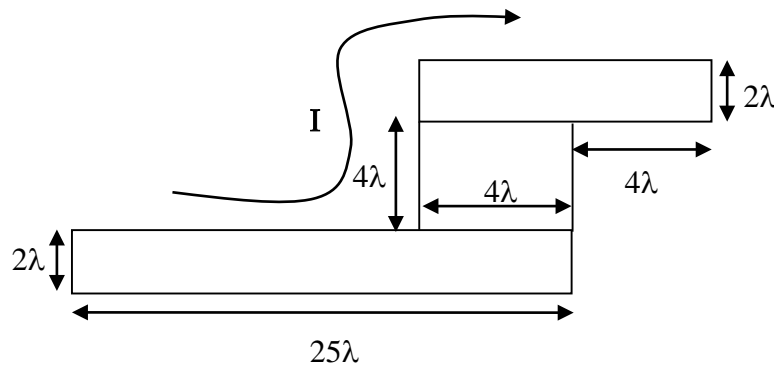


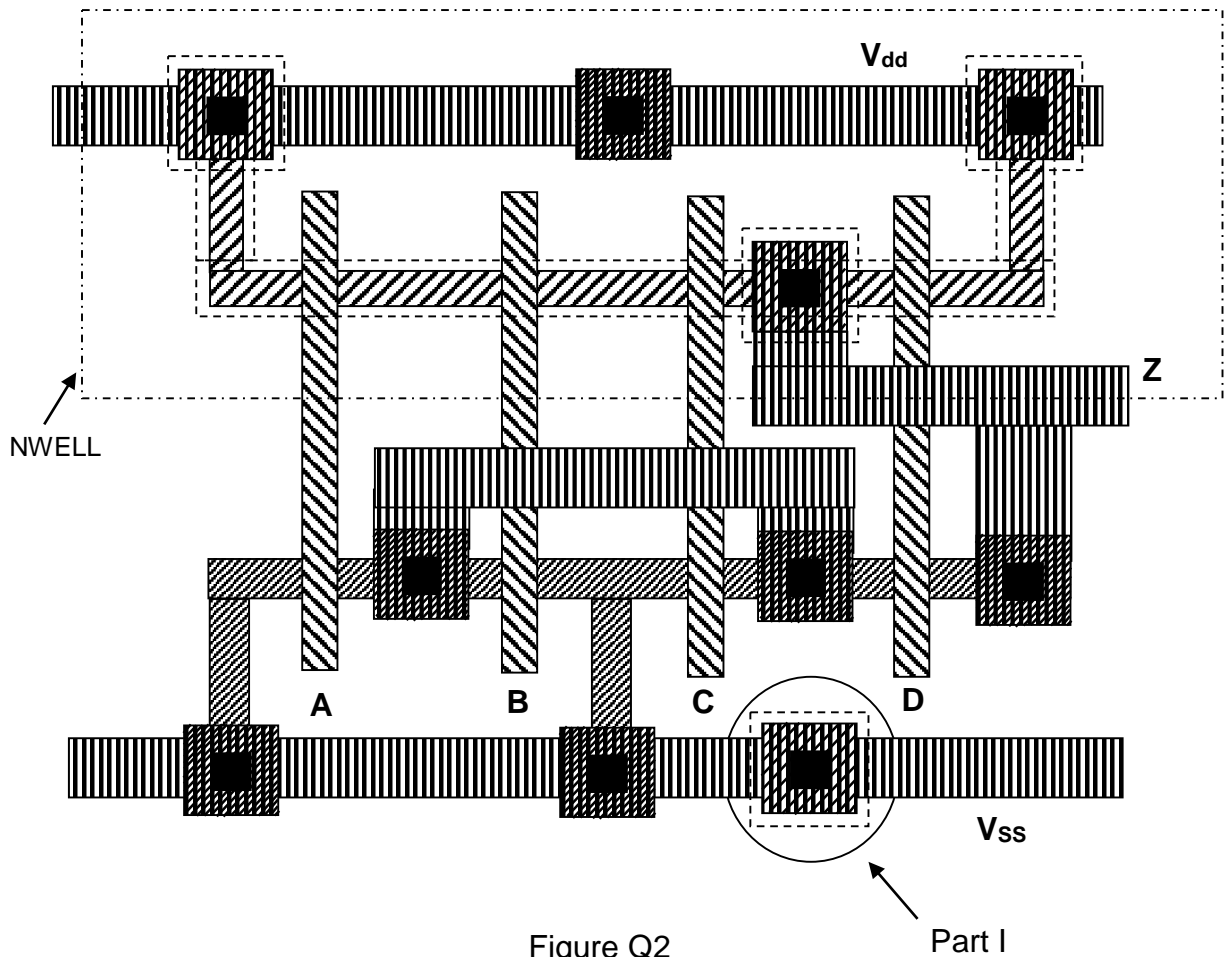
Figure Q1

- (b) Justify the following design rules:
- 2λ poly to poly spacing. (2 marks)
 - 2λ overhanging of polysilicon at transistor gate. (2 marks)
- (c) Latch-up is an inadvertent structure found in CMOS structure.
- Draw the latch-up equivalent circuit and explain what is latch-up. (5 marks)
 - Give two possible consequences when a latch-up occurs. (2 marks)
 - Suggest one method to minimize the occurrence of latch-up. (2 marks)

Question 2

For the mask layout of a CMOS circuitry shown in Figure Q2,

- draw its colour-coded stick diagram. (10 marks)
- name and explain the diffusion type used to form Part (I). State the purpose of Part (I) in a CMOS layout. (3 marks)
- what does the demarcation line in the stick diagram represent? (2 marks)
- why is diffusion not used for cross-well interconnections? (3 marks)
- draw its transistor level schematic and state the boolean equation for Z. (7 marks)



END OF SECTION A

SECTION B – ANSWER ANY 2 QUESTIONS (50 Marks)

Question 3

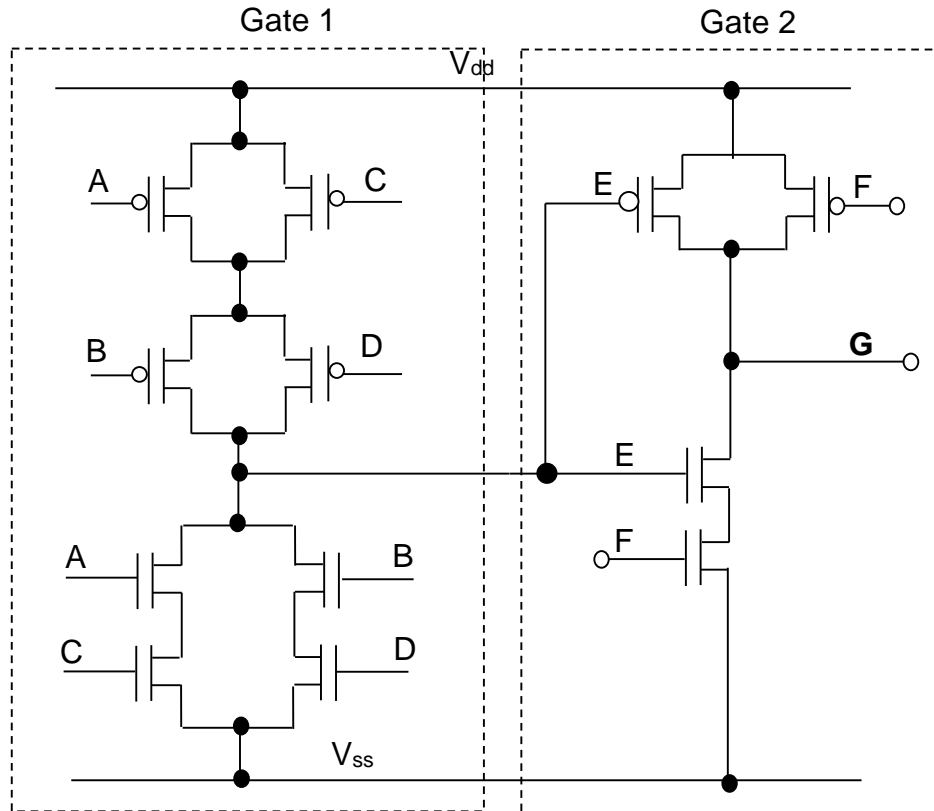


Figure Q3

- (a) For the CMOS complex gate shown in Figure Q3, state the boolean equation at point **G**. (5 marks)
- (b) Using the transistor sizes given in Table Q3, calculate the delay time from **D** to **G** for $A = B = F = 1$, $C = D = 0$ for a load of $3 \square C_g$. Give the answer in terms of τ where $\tau = R_{sn} \bullet \square C_g$ and $R_{sp} \approx 2.5 R_{sn}$.

(12 marks)

Gate	Transistor	Length (L)	Width (W)
Gate1	PMOS	2λ	16λ
	NMOS	2λ	2λ
Gate 2	PMOS	2λ	8λ
	NMOS	2λ	4λ

Table Q3

- (c) CMOS devices are known to be ratioless device, yet ratio is applied to the sizing of the various transistors as shown in Table Q3.
- Explain the purposes of having different sized PMOS and NMOS as shown. (2 marks)
 - Using relevant equations, explain how the size affects the path capacitance? (2 marks)
 - State 2 trade-offs when using larger transistors compared to smaller ones. (4 marks)

Question 4

- (a) Explain briefly the Write and Read operation of the 3-T DRAM cell shown in Figure Q4. (7 marks)

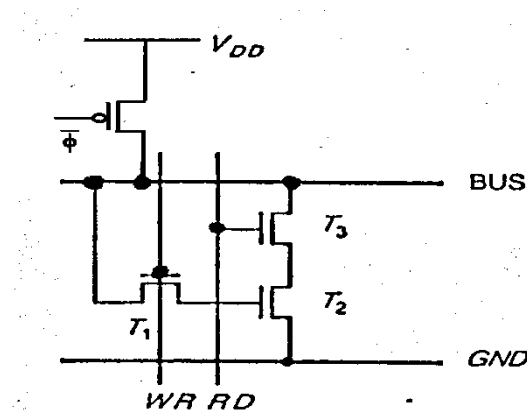


Figure Q4

- Explain briefly the need for sense amplifier in a RAM array. (3 marks)
- List three key differences between Static and Dynamic RAM. (6 marks)
- Explain briefly the propose of the following in integrated circuit (IC) design:
 - Test benches (2 marks)
 - Functional simulation (2 marks)
 - Logic synthesis (2 marks)
 - Design Rule Checker (3 marks)

Question 5

- (a) Name 3 semi-custom design techniques. Give one advantage and one disadvantage for each of the techniques named. (9 marks)
- (b) For the Verilog codes given in Figure Q5:
- (i) draw the block diagram and label the input and output pins. (4 marks)
 - (ii) is **Rst** a synchronous or asynchronous signal? Explain the purpose of this signal. (4 marks)
 - (iii) explain the functionality of the codes. (4 marks)

```
module Exam (Rst, Data, Clock, Q);
input Rst, Data, Clock;
output reg [3:0] Q;

always @(posedge Clock)
    if (Rst) Q <= 0;
else
begin
    Q[0] <= Q[1];
    Q[1] <= Q[2];
    Q[2] <= Q[3];
    Q[3] <= Data;
end
endmodule
```

Figure Q5

- (c) Two common approaches for digit circuit design are schematic capture and HDL approach. Name one advantage and one disadvantage for each of the approach. (4 marks)

END OF SECTION B

Mask Layout Encoding Table

LAYERS	MASK LAYOUT ENCODING	CIF LAYER
MONOCHROME		
n-diffusion (n ⁺ active)		ND
Polysilicon		NP
Metal 1		NM
Contact cut		NC
Overglass		NG
Implant		NI
Buried contact		NB
p-diffusion (p ⁺ active)		CAA or CPA
p ⁺ mask		CPP
Metal 2		CMS
VIA		CVA
NWELL		CPW
V _{DD} or V _{SS} CONTACT		CC

FEATURE	FEATURE (MASK) (MONOCHROME)
n-type enhancement transistor	
n-type depletion transistor	
p-type enhancement transistor	

Stick Diagram Encoding Table

Layer	Colour	Stick Encoding
n-diffusion	Yellow outline, Brown within	
p-diffusion	Dark Brown outline, Brown within	
Polysilicon	Green	
Metal 1	Blue	
Metal 2	Red	
Implant	Yellow dotted line	
Contact - Connect Poly to Metal 1 - Connect Diffusion to Metal 1	Black Solid circle	
Via - Connect 2 metals	Black	
*N-well / P-well boundary	Brown dotted line	
*Well tie / Substrate tie	Black Cross	

* only applicable to CMOS process